

L Number	Hits	Search Text	DB	Time stamp
1	1196	((polish\$3 abrad\$3 planari\$6)with immers\$4	USPAT	2004/04/02 08:08
2	0	((polish\$3 abrad\$3 planari\$6)with immers\$4)same magnet\$6 adj3 (solution agent)	USPAT	2004/04/02 08:10
3	23	(magnet\$6 adj4 (polish\$3 planariz\$6) adj4 (solution agent))	USPAT	2004/04/02 08:10
-	567	156/345.12 156/345.13 156/345.17 156/345.18 156/345.23	USPAT	2004/04/01 11:53
-	265	(156/345.12 156/345.13 156/345.17 156/345.18 156/345.23) and (edge peripheral periphery)	USPAT	2004/04/01 12:12
-	265	((156/345.12 156/345.13 156/345.17 156/345.18 156/345.23) and (edge peripheral periphery))	USPAT	2004/04/01 12:11
-	3116	134/1.3 134/135 134/902	USPAT	2004/04/01 12:12
-	1369	(134/1.3 134/135 134/902) and (edge peripheral periphery)	USPAT	2004/04/01 13:28
-	420	451/66 451/106 451/93	USPAT	2004/04/01 13:28
-	192	(451/66 451/106 451/93) and (edge peripheral periphery)	USPAT	2004/04/01 13:57
-	21	((polish\$3 planariz\$5 abrad\$3) with (edge peripheral periphery)) same magnet	USPAT	2004/04/01 14:22
-	3851	magnet\$6 with (polish\$3 abrad\$3 planari\$6)	USPAT	2004/04/01 14:34
-	17	"magnetic polishing"	USPAT	2004/04/01 13:46
-	332	((polish\$3 planariz\$5 abrad\$3) with (plurality stack) adj2 (wafers substrates))	USPAT	2004/04/01 13:56
-	248	((polish\$3 planariz\$5 abrad\$3) with (plurality stack) adj2 (wafers substrates))) and (edge peripheral periphery)	USPAT	2004/04/01 14:24
-	616	((polish\$3 planariz\$5 abrad\$3) same ("synthetic resin" "chloroprene rubber"))	USPAT	2004/04/01 14:23
-	324	((polish\$3 planariz\$5 abrad\$3) with ("synthetic resin" "chloroprene rubber"))	USPAT	2004/04/01 14:23
-	160	((polish\$3 planariz\$5 abrad\$3) with ("synthetic resin" "chloroprene rubber"))	USPAT	2004/04/01 14:24
-	21	and (edge peripheral periphery) magnet\$6 with (polish\$3 abrad\$3 planari\$6)with immers\$4	USPAT	2004/04/02 07:41